

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Satoshi Watanabe
Serial No.: to be assigned
Filed: concurrently herewith
For: *RESIST MATERIAL AND PATTERN FORMING METHOD*

Date: January 18, 2002

Commissioner for Patents
Washington, DC 20231

2/A
D.G.
3-26-02

PRELIMINARY AMENDMENT

Sir:

Prior to the examination of the above application, please amend the above-identified application as follows.

IN THE SPECIFICATION:

Please amend the specification as follows:

At page one, following the title " RESIST MATERIAL AND PATTERN FORMING METHOD", please insert

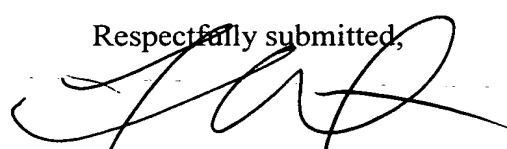
-- Related Application

This application claims priority from Japanese Patent Application No. 2001-012947, filed on January 22, 2001, the disclosure of which is incorporated by reference herein in its entirety.--

REMARKS

The above amendment is made to claim priority to the identified Japanese patent application.

Respectfully submitted,



F. Michael Sajovec
Registration No. 31,793